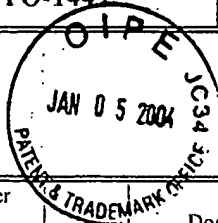


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### U.S. PATENT DOCUMENTS

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### FOREIGN PATENT DOCUMENTS

Examiner Initial	Document No.	Date	Country	Translation (Yes or No)
TSP	9-053188	2/97	Japan	Abstract

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